

Magnetron Sputter System

Model: SA-VKM600/M700

SA-VKM600 and SA-VKM700 are general-purpose magnetron sputter systems. Delivering high-performance, stable and reliable operation, they feature a high-level automated control system and easy-maintenance design to satisfy diverse magnetron sputtering process requirements for both production and R&D.



Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

Application

- Laser
- R&D
- Integrated circuit
- MEMS

Specifications:

Parameter	Descriptions
Number of Cathodes	5(max.)
Sputtering Power Supply	DC / RF / pulsed DC, freely switchable
Bias	RF / pulsed DC
Vacuum Sampling Chamber	Single-wafer / multi-wafer fully-automatic sampling chamber, optional
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Flow Control	Digital mass flow meter
Coating Uniformity	±2%
Coating Repeatability	±2%
Uniform Deposition Area	Ø300 mm(max.)
Ultimate Vacuum	8E-6Pa
Vacuum Measurement	Full-range vacuum gauge + Capacitance diaphragm gauge
Temperature Control Range	-50~800℃
Space Requirements(L×W×H,m)	3.2×3.3×2.2

Principle:

